

FULL SCALE INDUSTRIALIZATION OF SPS/FAST FOR MANUFACTURING ADVANCED CERAMICS

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The semiconductor manufacturing process has created one of the most extreme chemical and physical environments feasible through the use of halogen plasma dry etching for nano-fabrication. This environment requires ceramic chamber components of significant size (+600mm) that have exceptional chemical stability that produce zero defects on wafer. The extreme demands on semiconductor ceramics performance and supplier quality are the ultimate qualification for SPS as a manufacturing tool for making next generation material systems. Heraeus, a global supplier of semiconductor materials since the first transistor, has become the global leader in SPS manufacturing with more full scale production capacity than anywhere on the planet. The ceramic material requirements and development for etch applications will be discussed. In addition, the capabilities of high volume manufacturing a large scale ceramic product of exceptional quality using SPS will be demonstrated.

Professional Status of the Speaker

Senior Scientist

Interest in submitting a paper in a special issue of

No interest

Invitation letter for visa

No

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